IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

4083820481

Chiang, Tony P.; Leeser, Karl F.

Assignee:

Novellus Systems, Inc. (reassigned)

Title:

Method for Integrated In-Situ Cleaning and Subsequent Atomic Layer

Deposition Within a Single Processing Chamber

Serial No.:

09/994,279

Filing Date:

November 26, 2001

Examiner:

David Nhu

Group Art Unit: 2818

Docket No.:

PA1688 US

San Jose, California May 18, 2005

Mail Stop Amendment Commissioner for Patents

P.O. Box 1450 Alexandria, VA 22313-1450

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RESPONSE TO OFFICE ACTION

Dear Sir:

This responds to the Office Action dated February 4, 2005, in the above-identified application. A terminal disclaimer is enclosed. Please amend the application to place all claims in condition for allowance as follows.

Amendments to the claims begin on page 2.

Remarks begin on page 7.

05/25/2005 GST

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Ser. No. 09/994,279

PAGE 4/12 * RCVD AT 5/18/2005 6:44:55 PH [Eastern Daylight Time] * SVR:USPTO-EFXRF-1/5 * DNS:4729306 * CSID:4083820481 * DURATION (man-ss):103-18